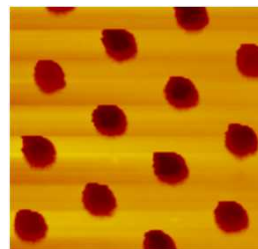
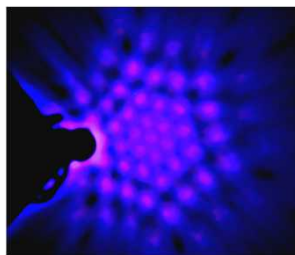


# Improved InGaN LED Efficiency Using Photonic Crystal Patterning and Surface Plasmon Enhanced Emission

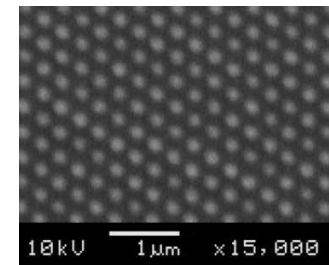
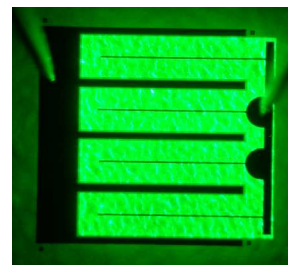
Arthur J. Fischer

**SANDIA NATIONAL LABS**

Albuquerque, NM



1  $\mu\text{m}$



Sandia is a multiprogram laboratory operated by Sandia Corporation, a Lockheed-Martin company, for the United States Dept. of Energy under contract DE-AC04-94AL85000



# Acknowledgements

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Sandia National Labs: A. J. Fischer, D. D. Koleske, G. R. Hadley, J. R. Wendt, J. A. Simmons, K. W. Fullmer, A. J. Coley, G. Thaler, M. Russell, and J. Figiel.

Lumileds Lighting: J. J. Wierer, M. R. Krames, M. G. Craford.  
- collaborated on photonic crystal LED research

University of New Mexico: D. Li and S. R. J. Brueck  
- collaborated on large area patterning- interferometric lithography

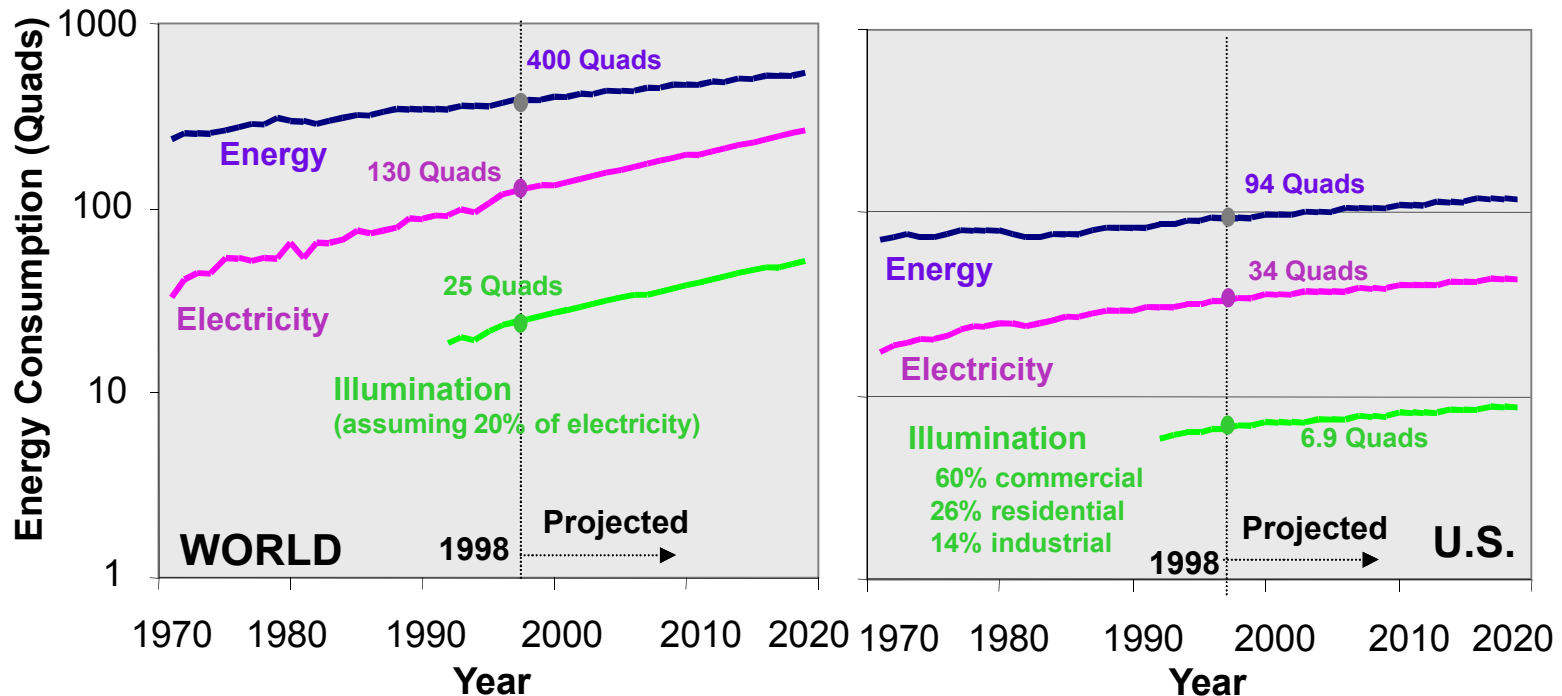
PX-LED and SP-LED Research at Sandia is  
funded, in part, by DOE – EERE



# OUTLINE

- I. Introduction
  - A. SSL energy savings potential
  - B. InGaN LEDs and SSL
  - C. Light extraction in semiconductors
- II. Photonic crystals and LEDs
  - A. Why use a photonic crystal in an InGaN LED?
  - B. Photonic crystal fabrication in GaN
  - C. Photonic crystal device results
- III. Surface plasmon LEDs
  - A. Surface plasmon LED device concept
  - B. Photoluminescence data
  - C. Electroluminescence data
- IV. Summary

# Lighting is responsible for a large fraction of energy consumption



- ~20% of electricity consumed is used for general illumination
- This 20% could be reduced to ~10% with 50% efficient SSL
- Reduced carbon emissions, fewer power plants, money savings



# SSL-LED Targets

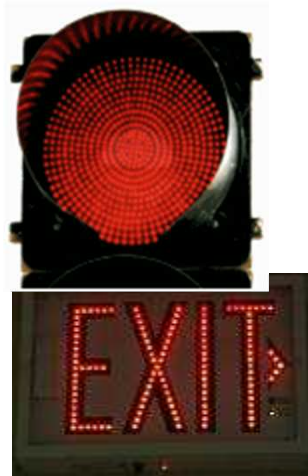
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- Performance goals (achieve by 2020)
  - Efficacy of 200 lm/Watt
  - Lifetime > 100,000 hours
  - Flux of 1500 lm/lamp
  - Cost of < 2 \$/klm
  - CRI of >80
- DOE Goal → reduce electricity for lighting by 50% by 2025

TECHNOLOGY	SSL-LED 2002	SSL-LED 2007	SSL-LED 2012	SSL-LED 2020	Incande- scent	Fluore- scent
Luminous Efficacy (lm/W)	25	75	150	200	16	85
Lifetime (hr)	20,000	>20,000	>100,000	>100,000	1,000	10,000
Flux (lm/lamp)	25	200	1,000	1,500	1,200	3,400
Input Power (W/lamp)	1	2.7	6.7	7.5	75	40
Lumens Cost (\$/klm)	200	20	<5	<2	0.4	1.5
Lamp Cost (\$/lamp)	5	<5	<5	<3	0.5	5
Color Rendering Index (CRI)	75	80	>80	>80	95	75

# Niche Applications for Ultrabright LEDs

Red LEDs 10X more efficient  
than red-filtered incandescents



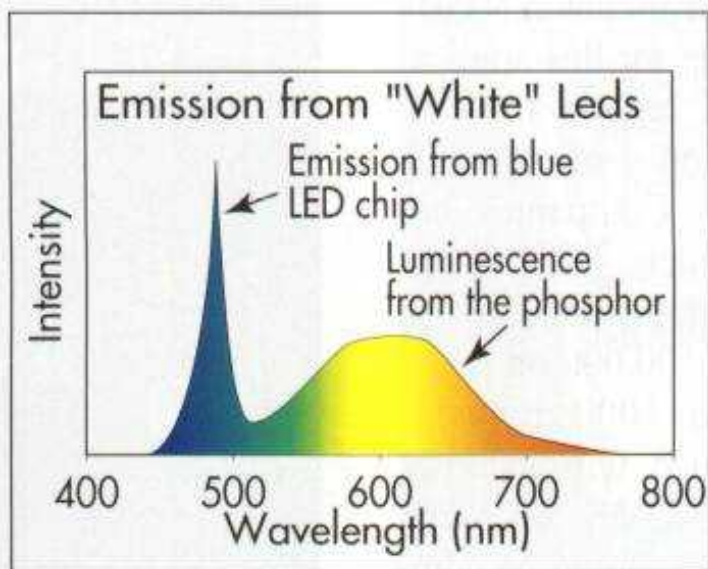
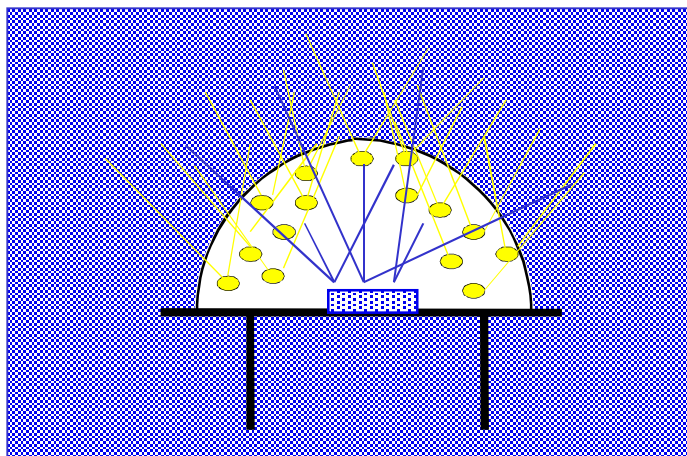
Programmable Lights on Ben Franklin Bridge,  
Philadelphia, courtesy of Color Kinetics



- Payback time for LED traffic lights is ~ 1 year
- Biggest market is outdoor signage and building contour lighting

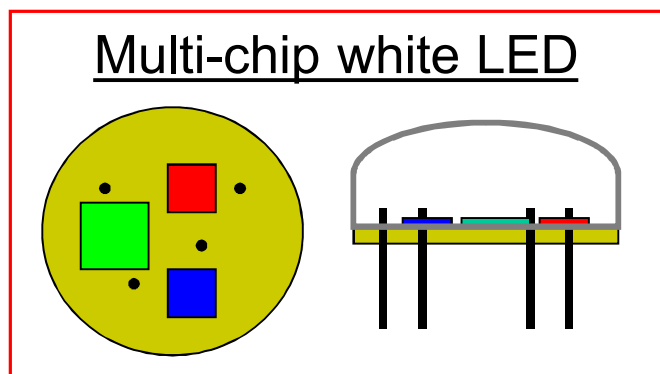
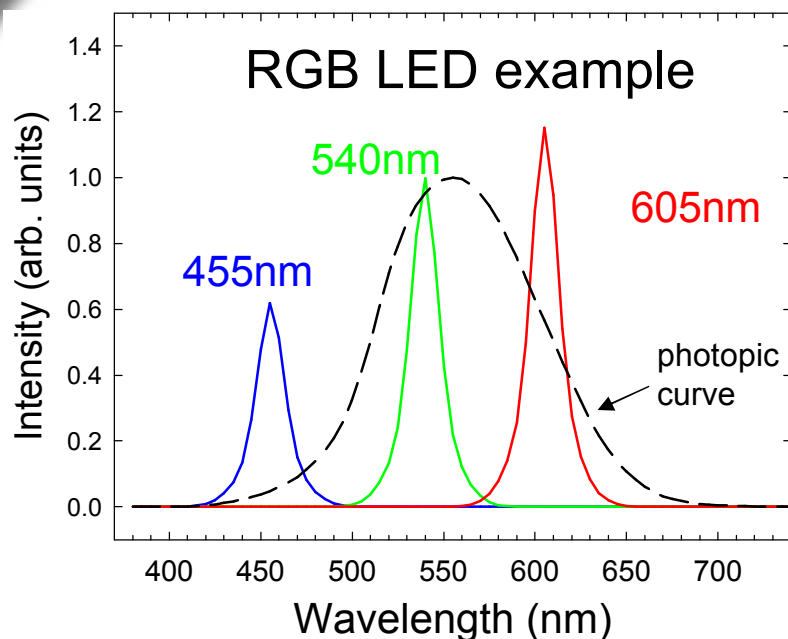


# White light LEDs (1): InGaN LED(s) + Phosphor



- Blue or UV LED pumps a phosphor
- Loss of energy converting blue photons to red
- Difficult to achieve 200 lm/W ?
- Most mature technology
  - Current products
    - **Large area (40 – 50 lm/W)**
      - Incandescent – 15 lm/W
      - Fluorescent – 90 lm/W
  - Research results\*
    - Small area ( 131 lm/W)
    - Large area ( 70 lm/W)
- Difficult to control colors
  - Angular color changes
  - LED to phosphor ratio may change with aging

## White light LEDs (2): Multi-chip approach

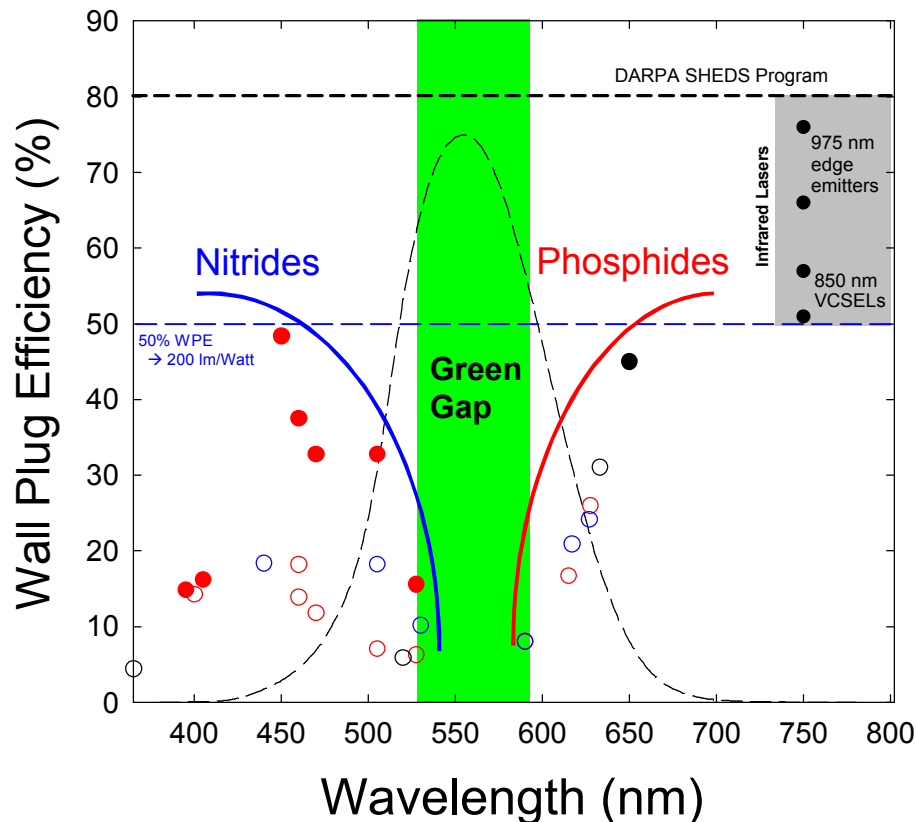


- Red, green and blue LEDs plus color mixing optics
- Could use four or more LEDs to get CRI > 90
- RGB example\* (shown in plot)
  - Assumes 50% WPE LEDs
  - CRI 80
  - **197 lm/W**
- Potential for highest efficacies
- No phosphor losses
- Aging of different material systems ?
- Control electronics ?

\*Calculated using Y. Ohno's white LED simulator



# Semiconductor-based light emitters have the potential to exceed 50% efficiency across the visible



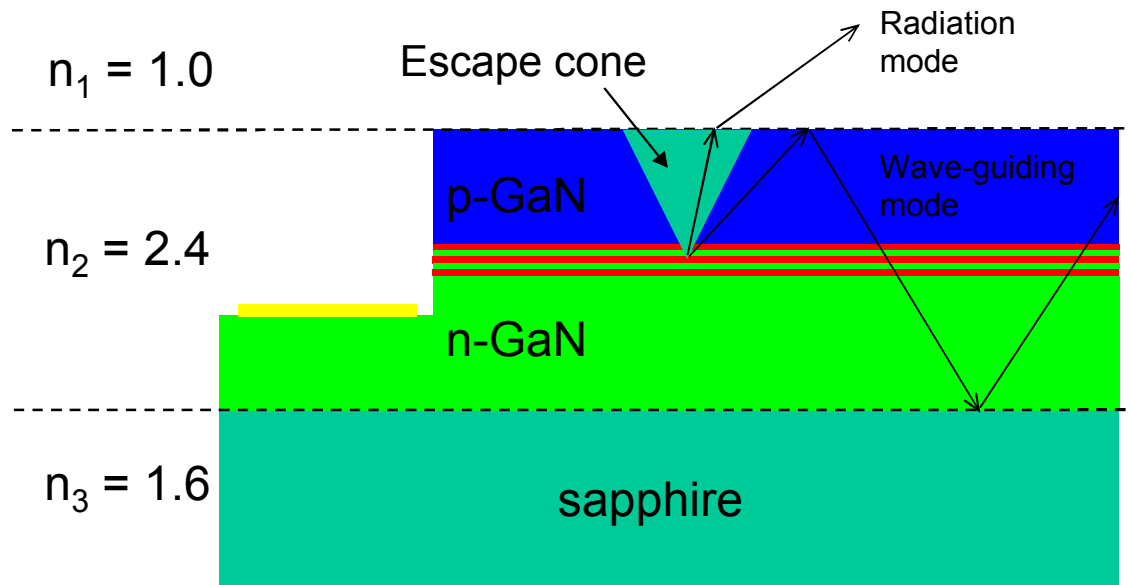
- ~ 50% WPE demonstrated for blue and red
  - Phosphide-based LEDs\*
    - (45% WPE, 650nm)
  - Small area InGaN LEDs†
    - (50% WPE, ~460nm)
- Lasers in the IR have already demonstrated > 70% WPE
  - JDSU (76% WPE, 950nm)
  - Alphalight (73% WPE, 975nm)
- IQE needs improvement (green and yellow)
- Need improvements to light extraction

\* M. R. Krames et al. Appl. Phys. Lett, **75**, 2365 (1999)

† press release → [www.cree.com](http://www.cree.com)

# Light Extraction Problem in LEDs

- Photons are trapped inside the high index layer (TIR)
- With high IQE, photon recycling can help extraction
- For lower IQE materials
  - non-radiative recombination is significant
  - more internal reflections  $\rightarrow$  more chance of absorption
  - better to get the photons out with a minimum of reflections
- Without advanced light extraction techniques, LED efficiency is usually quite low



The escape cone is defined by the critical angle:

$$\theta_{CRIT} = \sin^{-1}\left(\frac{n_1}{n_2}\right) = 24.6 \text{ deg}$$

$$\eta_{EXT} = \frac{\text{escape cone solid angle}}{\text{total solid angle}}$$

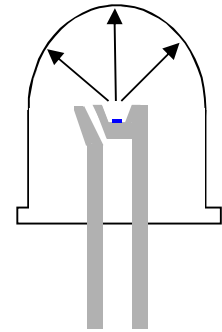
$$= \frac{2\pi \left[ 1 - \cos\left(\sin^{-1}\left(\frac{n_1}{n_2}\right)\right) \right]}{4\pi}$$

$$\sim \frac{n_1^2}{4n_2^2} = 4.3\% \text{ (per surface)}$$

# Methods of light extraction

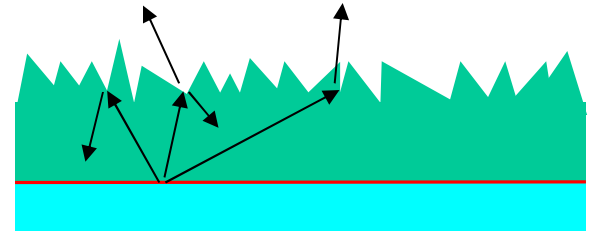
## Epoxy encapsulation

- Reduce index step from Semiconductor to air
- Create a favorable geometry
- High index encapsulants are desired
- Issues of transparency and thermal degradation



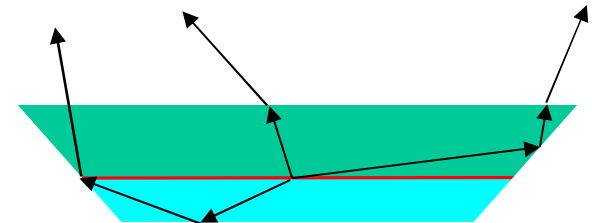
## Surface Texturing

- Random scattering at surface
- Some fraction of light scatters out
- light scattered back inside can be absorbed



## Chip Shaping

- Modify chip to improve light extraction
- Angle chip sides to redirect waveguided light
- Long path length → possibility for absorption

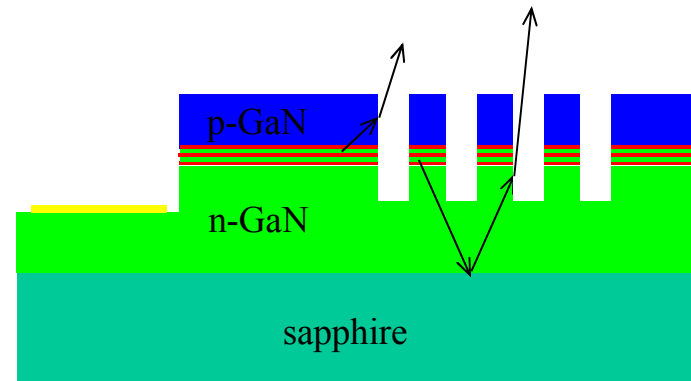


## Photonic Crystals...

# Photonic Crystals for Light Extraction

- Etch a photonic crystal into the surface of an LED
- Photonic crystal can improve extraction two ways
  - 1.) Inhibit emission into waveguiding modes
    - Requires very small lattice constant (  $\sim 100\text{nm}$  )
    - 2D photonic bandgap in the plane
  - 2.) Bragg scatter waveguided light out of semiconductor
    - Relaxed lattice constants (200 – 500 nm)
- Immediate diffraction of light (not random scattering)
- Eliminate encapsulant
- Increase source brightness

**Light extraction with  
a photonic crystal**



# Characteristic hole sizes for PX-LEDs

- First order gratings will be difficult to fabricate in GaN
- Diameter = 0.6 X lattice constant ( $d = 0.6 \cdot a$ )
- Hole sizes are smaller for shorter wavelengths (or larger indices)

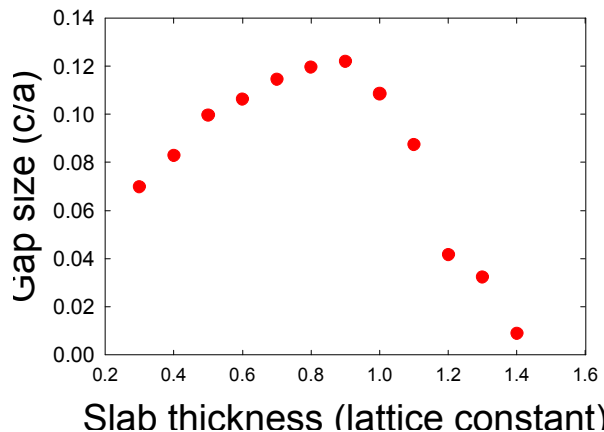
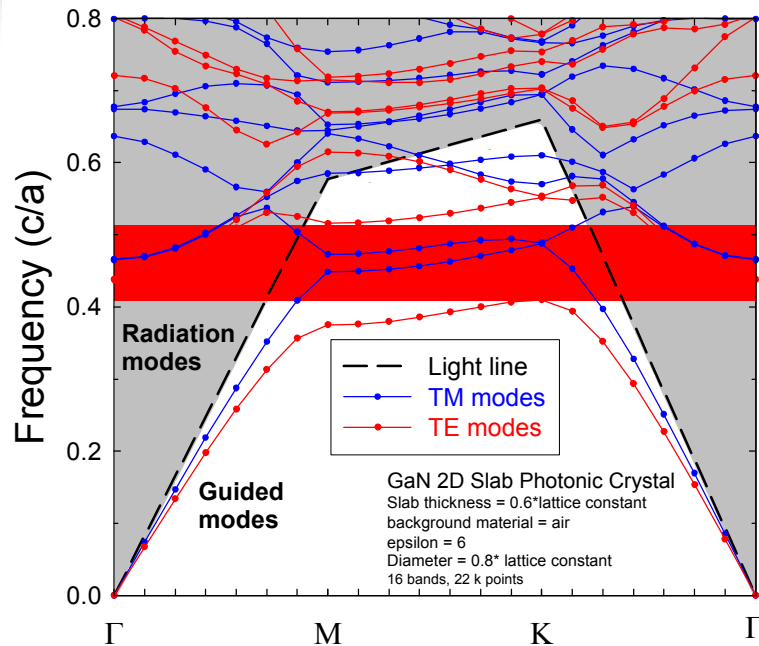
## **1.) InGaAs LED - 980 nm emitter**

		<u>period (a)</u>	<u>diameter (d)</u>
Requirements for $\lambda$	$\rightarrow (\lambda_0/2n)$ <u>1st order</u>	144 nm	86 nm
fixed at 980 nm	$(\lambda_0/n)$ <u>2nd order</u>	288 nm	173 nm
( $n = 3.4$ )	$(2\lambda_0/n)$ <u>4th order</u>	576 nm	346 nm

## **2.) InGaN LED - 460 nm emitter**

		<u>period (a)</u>	<u>diameter (d)</u>
Requirements for $\lambda$	$\rightarrow (\lambda/2n)$ <u>1st order</u>	96 nm	58 nm
fixed at 460 nm	$(\lambda/n)$ <u>2nd order</u>	192 nm	115 nm
( $n = 2.4$ )	$(2\lambda/n)$ <u>4th order</u>	383 nm	230 nm

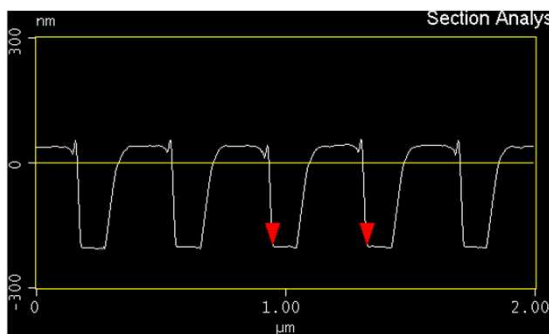
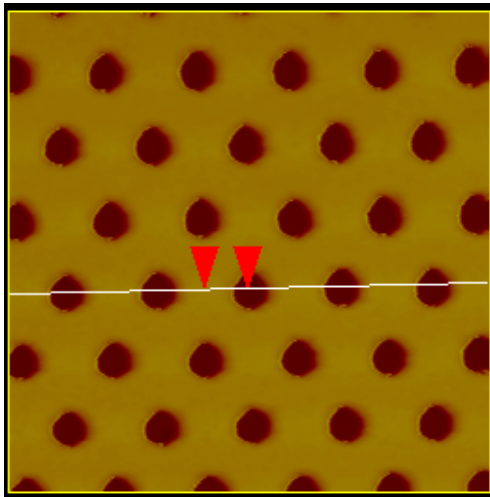
# GaN thin slab band structure calculations



- Band structure calculated using MIT photonic bands software (also Optiwave)
- Gap only for TE modes for most structures
- GaN slab suspended in air with holes etched all the way through
- Triangular lattice of holes
- TE-like gap from 0.41 to 0.51 c/a
- For a 450 nm LED
  - gap is centered at 450 nm for  $a=207$  nm,  $d=165.6$  nm
  - TE-like gap 406 nm  $\rightarrow$  504 nm
- Calculation assumptions:
  - Hole diameter =  $0.8 \times$  lattice constant
  - Epsilon = 6 for GaN
  - Background material is air
- Gap for thin slabs only
  - Slab must be less than 400 nm
  - This is the thinnest GaN slab we have made

# E-beam lithography for GaN Photonic Lattices

## Photonic Lattice in GaN

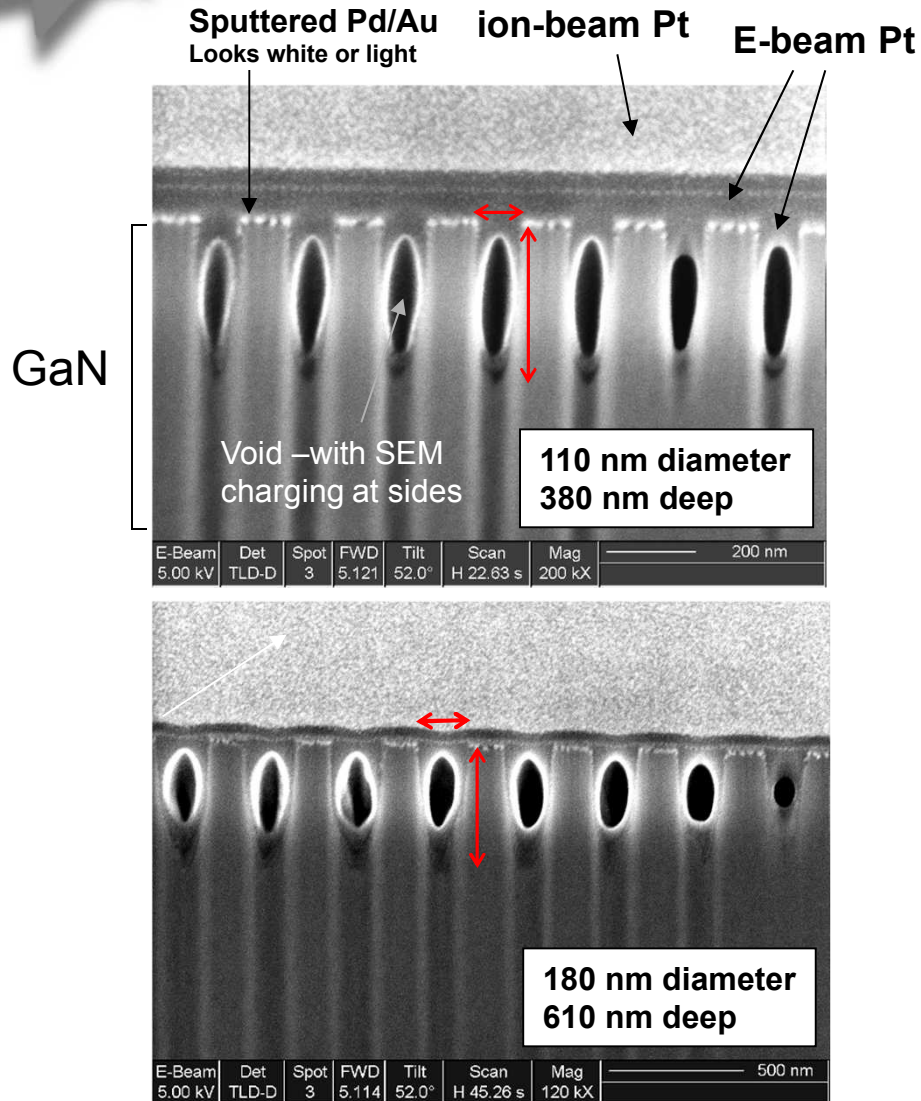


- Electron beam patterning is slow
  - ~ 1 hr for ea. 1 x 1 mm<sup>2</sup>.
  - Demonstrate PX-LEDs
- Wafer scale patterning
  - Large area LEDs
  - Production
  - Accelerate research
  - Large area patterning techniques
    - Interferometric lithography (UNM)
    - Nano-imprint lithography
    - Deep UV lithography

$d \sim 160\text{nm}$   
 $a \sim 380\text{nm}$   
 $r/a \sim 0.21$



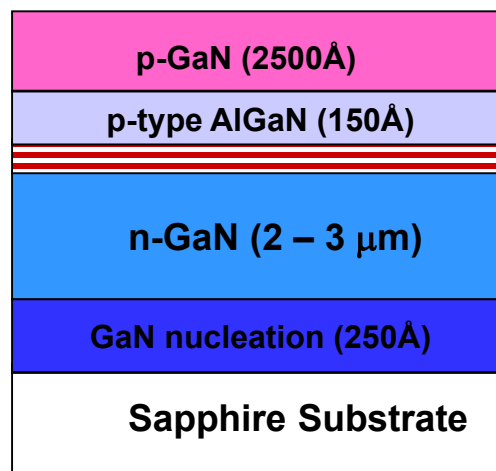
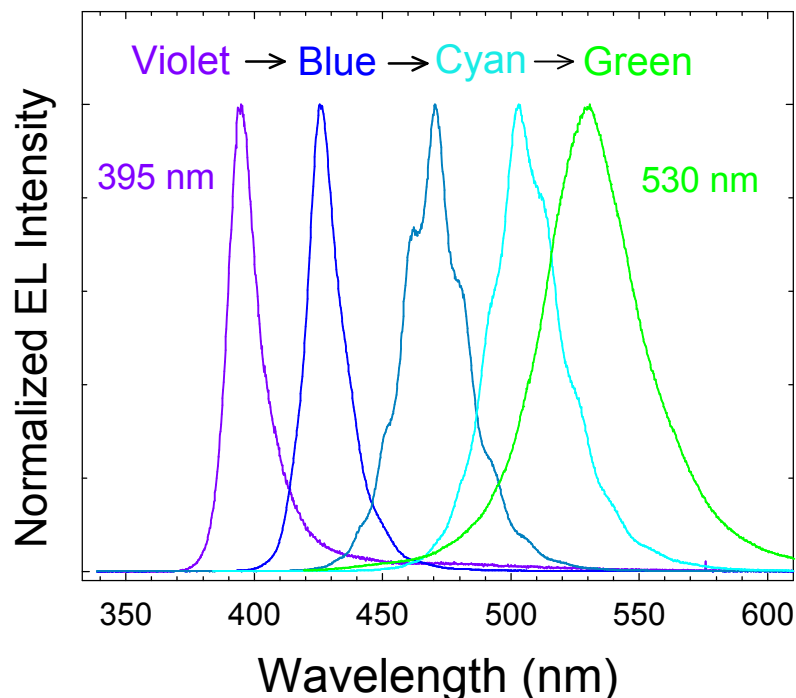
# Photonic Crystal Fabrication in GaN



- These images represent the best etching we have done to date.
- Top Image
  - 205 nm lattice constant
  - 110 nm in diameter
  - 380 nm deep
  - 3.45 : 1 aspect ratio
- Bottom Image
  - 315 nm lattice constant
  - 180 nm in diameter
  - 610 nm deep
  - 3.39 : 1 aspect ratio
- FIB-SEM used for characterization
  - Images taken with a tilt of 52°
  - Note that scale bars are different in the two images
- Very straight sidewalls- particularly for the 110 nm diameter holes
- Etch mask has been removed

# Sandia InGaN LED Development

- Sandia LEDs grown using one of two Emcore D-125 reactors
- LEDs from near UV (380 nm) to green (530 nm)
- Also developed deep UV LEDs (237 nm – 300 nm)
  - Based on AlGaN with high Al content
- Working to improve green LED efficiency



## Active Region:

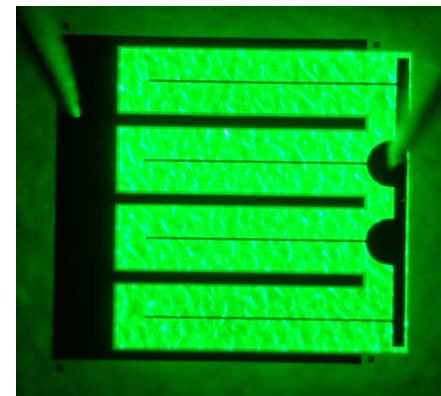
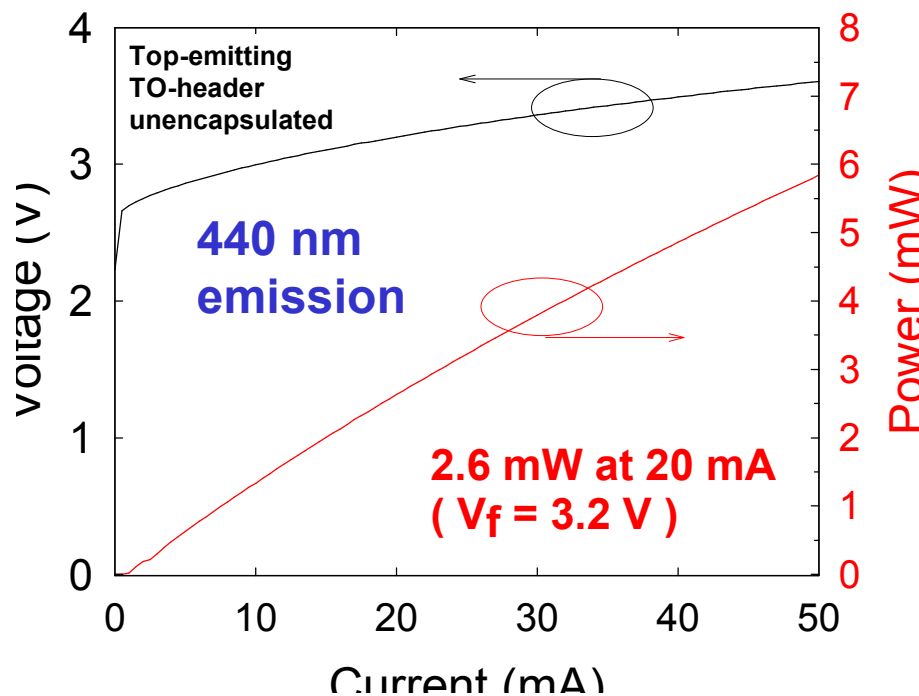
1 - 5 quantum wells

QWs: 20 – 30 Å  $\text{In}_x\text{Ga}_{1-x}\text{N}$   
 $x = 0.05 - 0.20$

Barriers: 75 – 150 Å GaN

# Sandia InGaN LED Development

- Sandia uses research grade packaging
  - TO-headers with no encapsulation
- Top-emitting LEDs with a transparent contact are used as a metric for LED development.
- Encapsulation can show 2X increase in power
- Developed a simple flip-chip process (2X power)

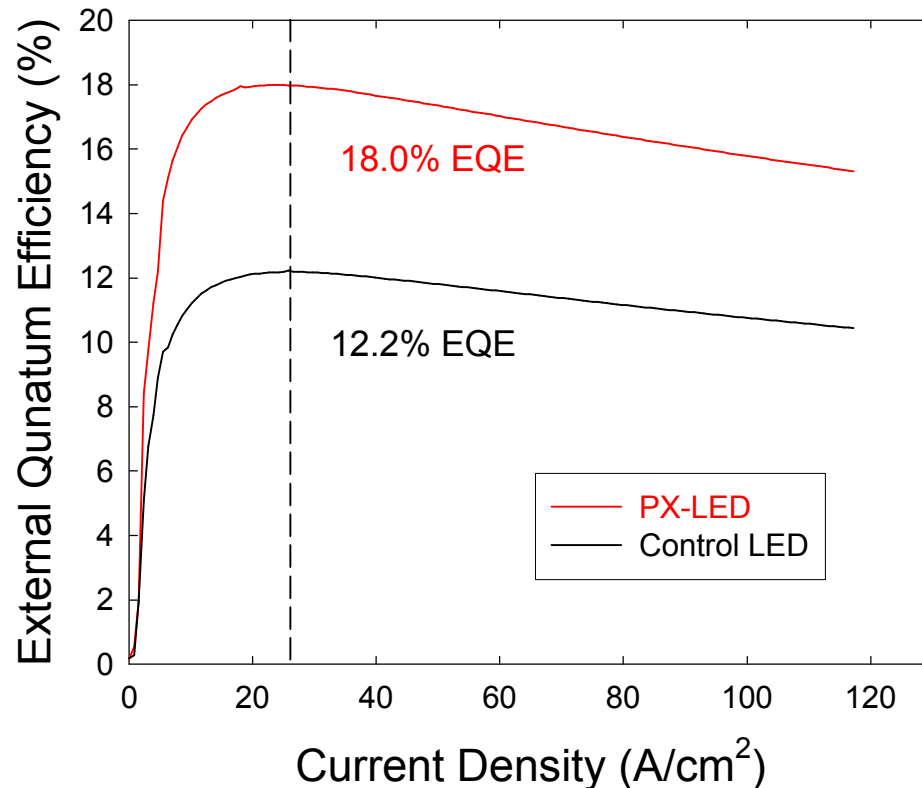


Sandia top-emitting green LED with transparent contact



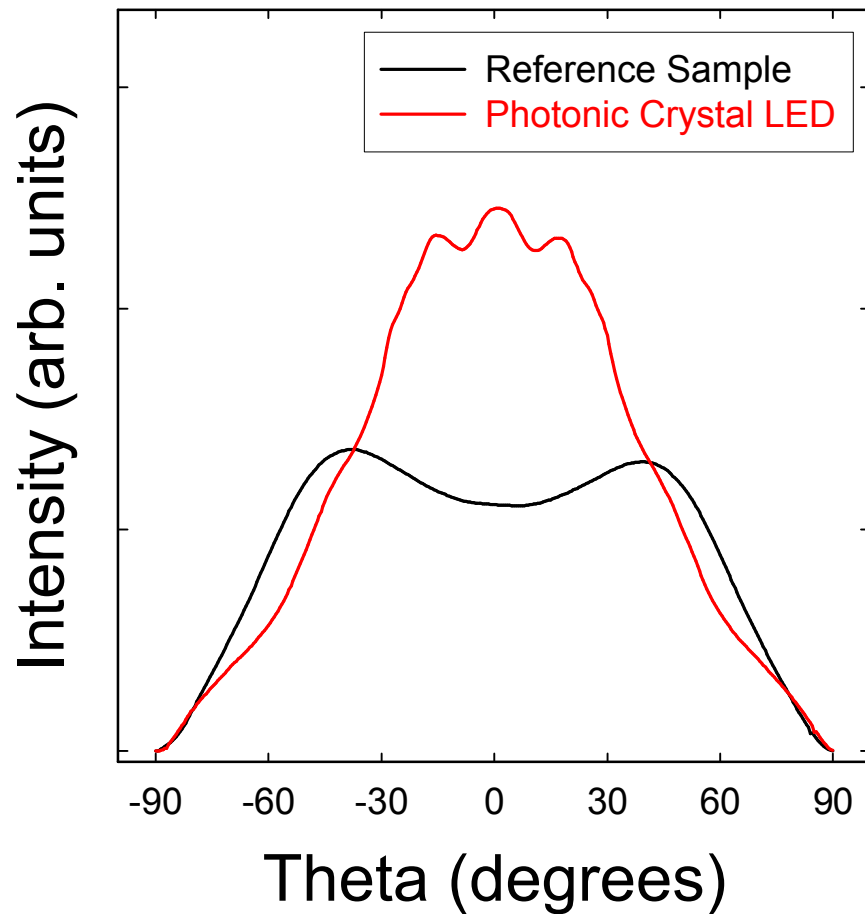
Sandia flip-chipped InGaN LED on TO-header

# Efficiency of small area InGaN PX-LEDs



- Small area LEDs fabricated using e-beam lithography for patterning
- LEDs were mounted on TO-Headers and left unencapsulated
- Total light emission was measured using a calibrated integrating sphere.
- low current densities (25 A/cm²)
  - PX-LED → 18.0% EQE
  - Control LED → 12.2% EQE
  - 1.48 X increase in power
- Higher current densities (100 A/cm²)
  - PX-LED → 15.8% EQE
  - Control LED → 10.8% EQE
  - 1.46 X increase in power
- LEDs for SSL will be run at high current densities

# PX-LED Fabrication : Enhanced brightness from PX-LEDs



- Angular measurements were performed on a large number of samples
- Angular data could be used to rapidly measure output power without dicing and packaging
- LEDs mounted on TO-headers were compared to devices on wafer
- Photonic crystal LEDs can be used to direct more light in the forward direction and increase source brightness.
- Far field patterns are strongly modified for PX-LEDs
- Photonic crystal is diffracting waveguiding modes into the escape cone

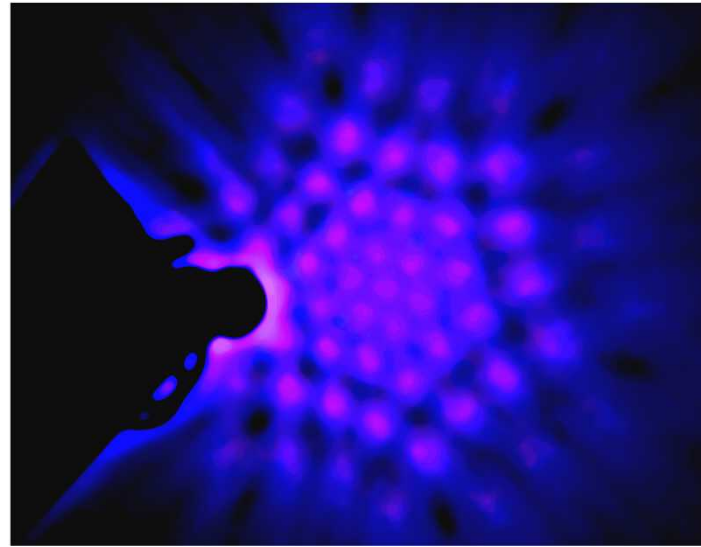
# PX-LED Far Field Patterns

- Small area photonic crystal LEDs
- LEDs were mounted on TO-headers
- Emission pattern was projected onto a piece of white paper
- Far field patterns are strongly modified for PX-LEDs
- Photonic crystal is diffracting waveguiding modes into the escape cone

**Control LED – No Photonic Crystal**



**LED with Photonic Crystal**

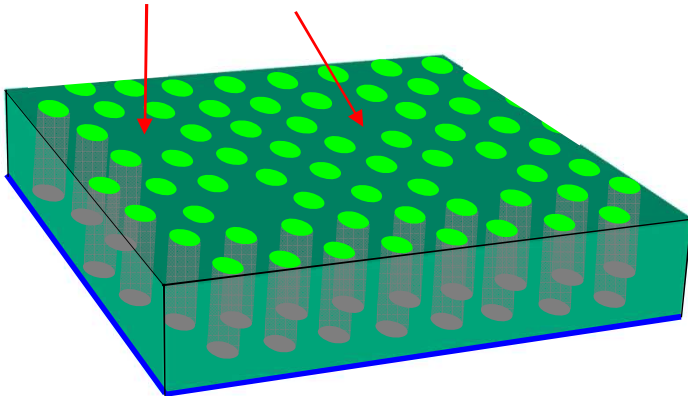




# PX-LED with defect cavities

## Planar microcavity plus in-plane defect cavities

Missing holes form defect cavities



PX-LED semiconductor slab  
with a an array of defect cavities

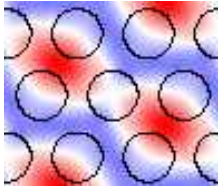
- Design a photonic lattice with an array of missing holes
- Combined with a planar microcavity will form a 3D cavity
- FDTD calculations indicate that very high extraction should be possible
- First order grating probably required
  - 150 nm pitch
  - In-plane photonic bandgap
- Resonant injection into defect cavities
  - Bypasses issues of current leakage
- Very promising advanced design



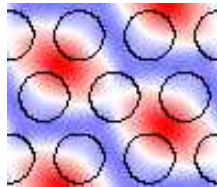
# Defect cavity electric field calculations

## Simple triangular lattice:

$E_x$  of TE band 1



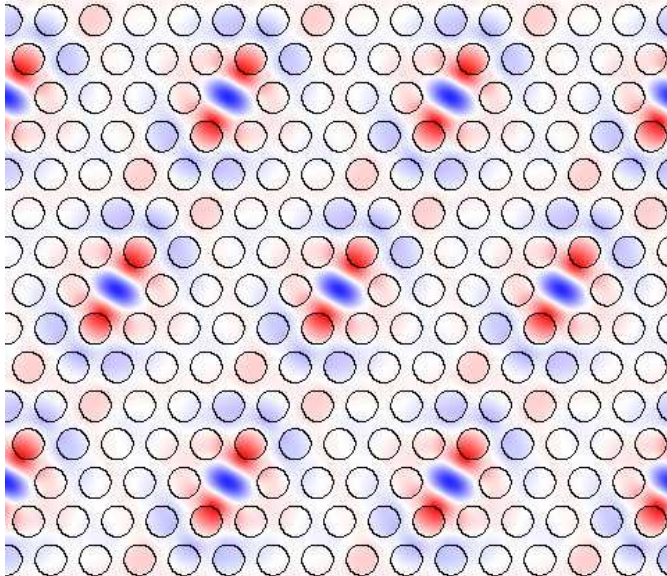
$E_y$  of TE band 1



- Calculate the spatial Electric field distribution for defect cavities in GaN
- Calculated using MIT photonic bands software (also using Optiwave)
- Triangular lattice of holes with a missing hole every 5 lattice constants
- For a simple triangular lattice the field extends across many lattice constants
- **Defect cavities do a good job of confining the radiation for modes in the gap**
- Lateral propagation is minimal

## Arrays of Defect Cavities:

$E_x$  component of TE band number 26



### Calculation parameters

Triangular lattice of air holes etched in GaN

Epsilon of GaN = 6.0

Defect cavity every 5 lattice constants

Diameter/lattice constant = 0.7

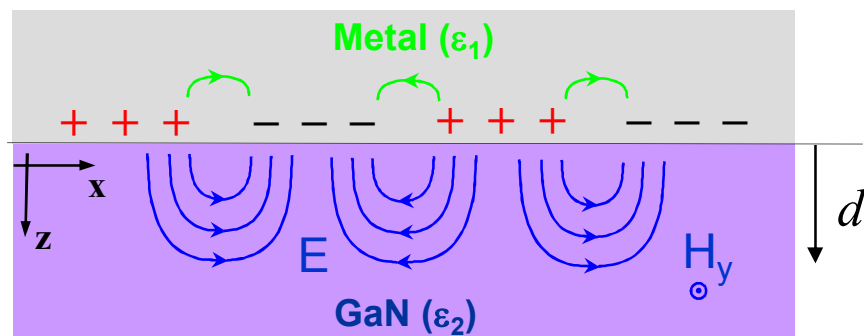
Two dimensional calculation

# Introduction to Surface Plasmons

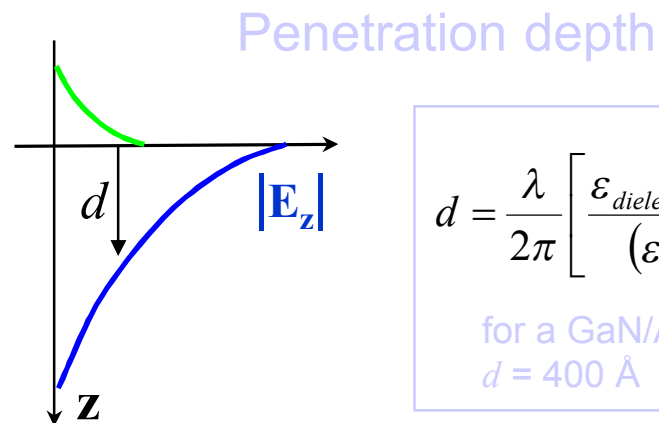
Bulk Plasmon → Collective oscillation of electronic charge in a material

Surface Plasmon →

- Combined EM wave and surface charge oscillation
- Excitation confined to the interface
- Exponential decay of electric field from the interface
- Transverse magnetic in character
- Mixed longitudinal and transverse E-field
- $\epsilon'_1$  and  $\epsilon'_2$  must have opposite signs



$$E = E_0^{\pm} \exp[ik_x x \pm k_z z - i\omega t]$$

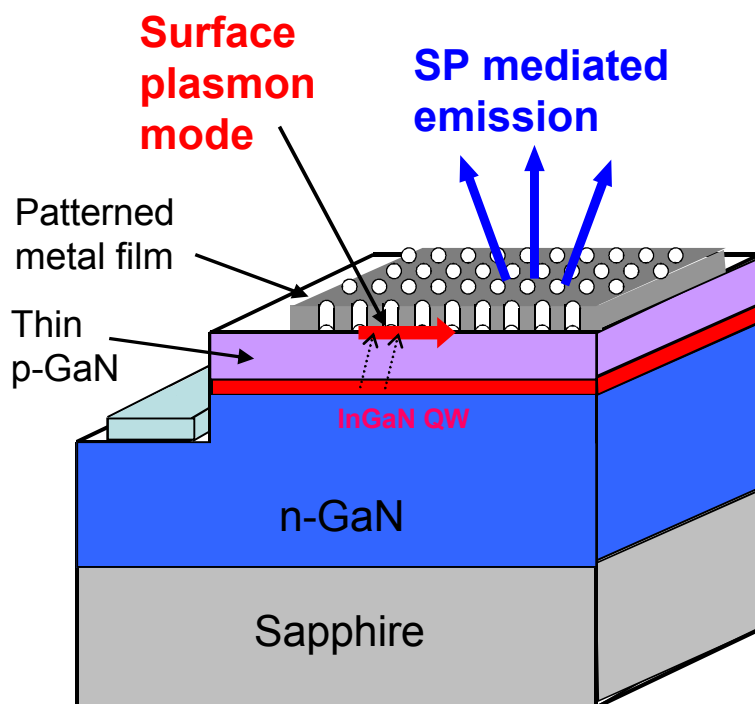


$$d = \frac{\lambda}{2\pi} \left[ \frac{\epsilon_{dielectric} - \epsilon_{metal}}{(\epsilon_{dielectric})^2} \right]^{\frac{1}{2}}$$

for a GaN/Ag interface  
 $d = 400 \text{ \AA}$

# Surface Plasmon Light Emitting Diodes

## InGaN Surface Plasmon LED



### Device Design:

#### Step one – coupling of QW to SP mode:

- Single QW close to air interface
- Thin p-GaN (100 – 500Å)
- Match SP energy to QW emission

#### Step two – extraction of SP mode:

- Patterned metal film for extraction
- Metal also provides current injection

### Advantages of Design:

- Improved IQE (green LEDs)
  - rapid coupling from QW to SP
- Same design improves IQE and extraction
- Enhanced IQE using existing materials

### Primary Challenges:

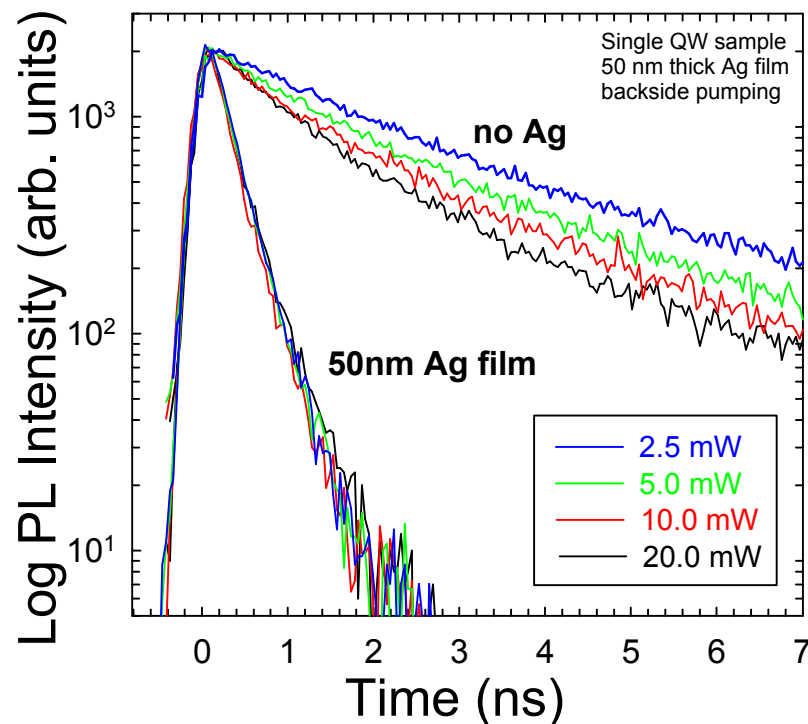
- QW placement near surface
- Design of patterned metal film

# Time-resolved Photoluminescence

## TRPL Measurements:

- Single quantum well samples- 10nm GaN cap
- Various metal films were deposited (Ag, Pt, Ni, Au)
- For data here,  $\tau_{\text{Ag}} = 0.28\text{ns}$  and  $\tau_{\text{noAg}} = 2.75\text{ns}$
- Shows rapid coupling from QW to SP modes
- Measurements were performed using backside pumping and collecting through the sapphire substrate
- Significant changes in PL decay time are possible
- PL lifetime can be longer or shorter depending on surface plasmon extraction.

## PL decay measurements



**Increase spontaneous rate → energy  
is effectively coupled to SP modes**

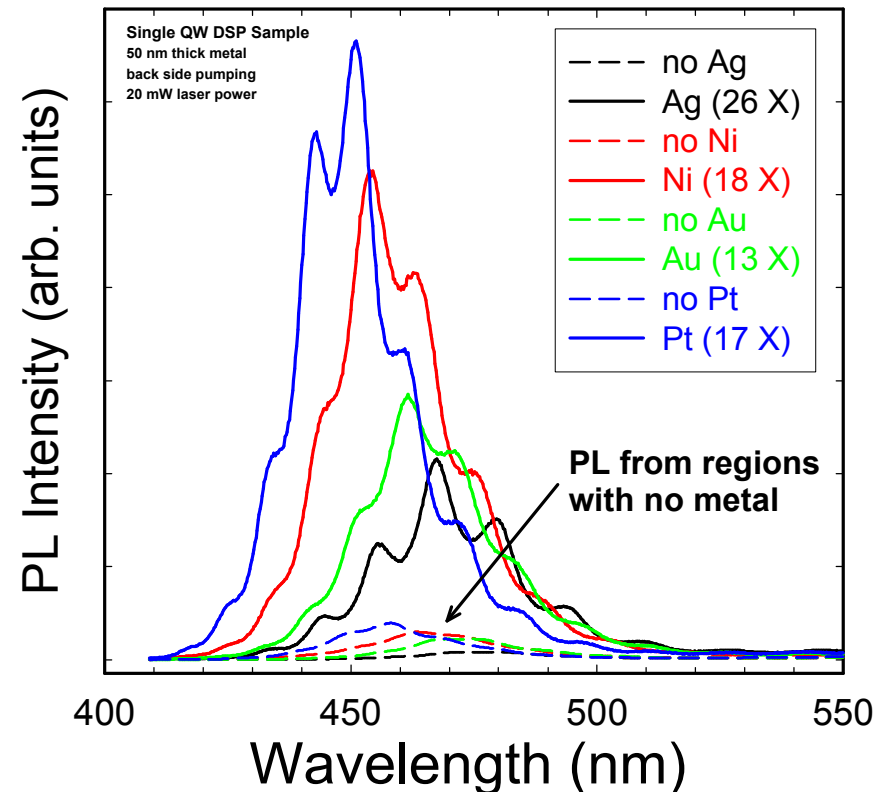
# Time-Integrated Photoluminescence

## TIPL Measurements:

- Single quantum well samples- 10nm GaN cap
- Various metal films were deposited (Ag, Pt, Ni, Au)
- Peak PL enhancements up to 26 times were observed
- Measurements were performed using backside pumping and collecting through the sapphire substrate
- Surface plasmon enhancements were greater at higher pump densities
- Scattering due to surface roughness improves coupling of light out of sample

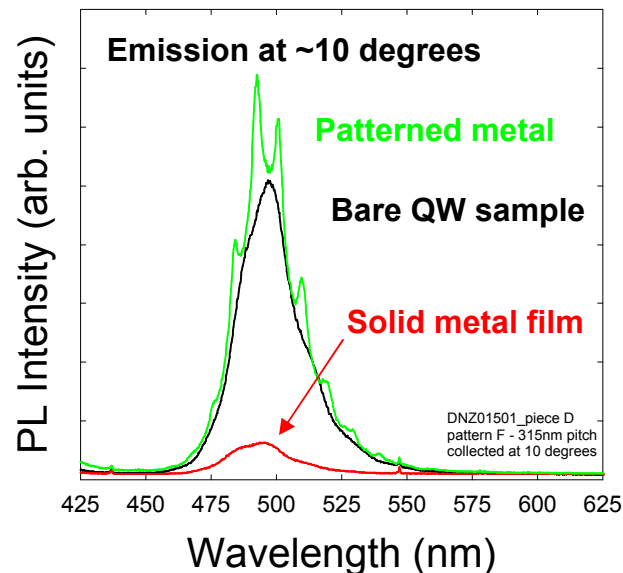
**Increase in total PL intensity → light is effectively extracted from SP modes**

## PL using different metals



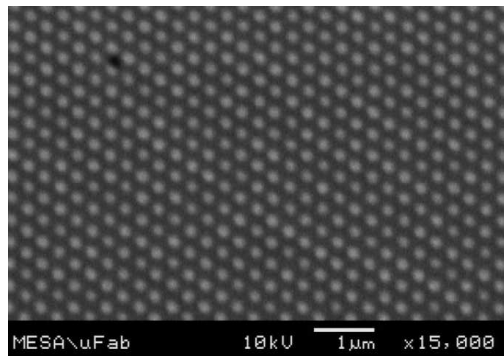
# Photoluminescence from patterned samples

## PL from pattern Ag InGaN QW sample



- This sample shows decreased emission due to surface plasmon effects.
- QWs couple to SP modes but light cannot escape.
- Data shown is angularly resolved PL data collected using a fiber position over sample.
- Regions with patterning show an increase in PL intensity.
- Increase is for certain directions and angles consistent with Bragg scattering.
- Surface texturing may work just as well as photonic lattice patterning.

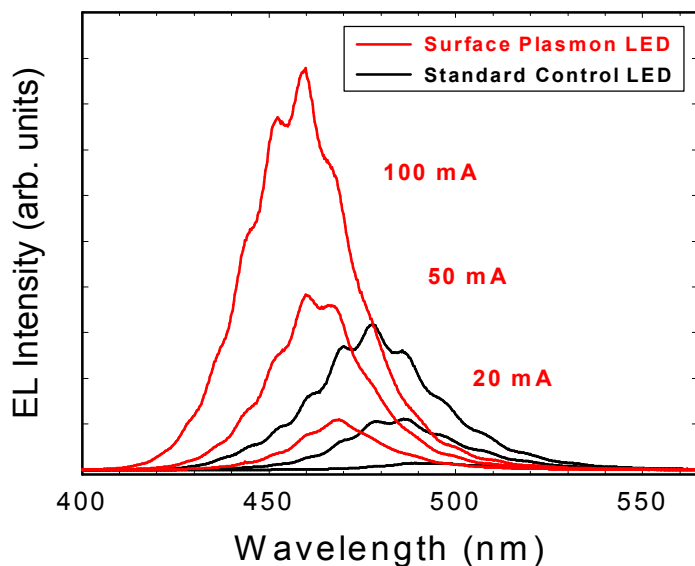
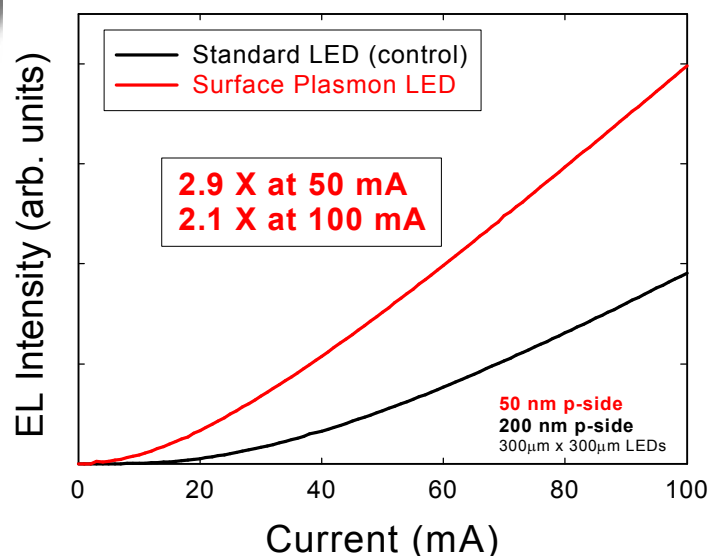
## Patterned Ag disks on InGaN QW sample



**Patterning or texturing will be required for samples with smooth interfaces**



# Electrically Injected Surface Plasmon LEDs



## Surface Plasmon LED data:

- LEDs were grown with different p-side thicknesses (20 nm  $\rightarrow$  200 nm)
- Regrow different top LED structures on identical GaN templates
- LEDs with a very thin p-side are expected to show surface plasmon enhancement
- SP-LEDs show a large blue shift in their emission spectra
- **LED output power is enhanced by 2 to 3 times**





# Summary and Future Work

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## Summary

### Photonic crystal LEDs:

- Fabricated 2D photonic crystals in GaN material
  - 110 nm diameter, 380 nm deep, > 3:1 aspect ratio
- Incorporated Photonic Crystals in Electrically injected LEDs
- Demonstrated a 1.5X increase in total LED power
- Far field patterns are strongly modified due to photonic crystal

### Surface plasmon LEDs:

- Showed increase in total PL intensity using surface plasmon effects
- Demonstrated changes to the radiative lifetime using TRPL
- Demonstrated a 2 – 3 times increase in LED power using SP-LEDs

## Future Work

- 2D photonic crystals with smaller, deeper holes
- PX-LEDs** • Defect cavity photonic crystal LEDs
- Utilize Purcell effect, inhibited lateral modes
- Explore alternate metalization schemes for SP-LEDs
- SP-LEDs** • Move to longer wavelengths (green InGaN emitters)
- Fabricate devices with patterned (or textured) metal